

## Patent Abstracts of Japan

PUBLICATION NUMBER : 2000021748  
PUBLICATION DATE : 21-01-00

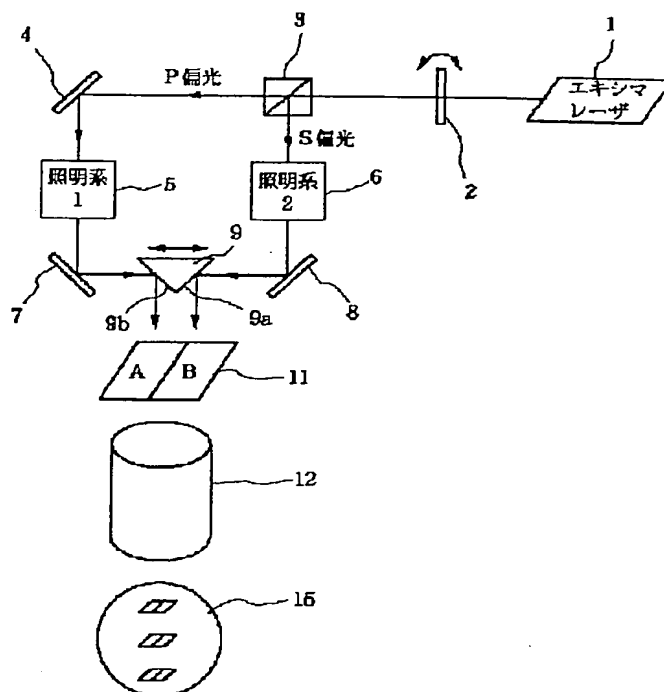
APPLICATION DATE : 30-06-98  
APPLICATION NUMBER : 10199769

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INT.CL. : H01L 21/027 G03F 7/20

TITLE : METHOD OF EXPOSURE AND  
EXPOSURE EQUIPMENT



**ABSTRACT :** PROBLEM TO BE SOLVED: To expose plural patterns to a substrate to be exposed to produce a superposed pattern on a same shot by dividing a luminous flux emitted from an exposure light source into plural ones and making each divided luminous flux illuminate a mutually different area of an exposure field by adjusting desired illuminating conditions for each.

**SOLUTION:** A linearly polarized beam emitted from a laser beam source 1 is converted into a circular polarized beam by a  $\lambda/2$  plate, and is launched to a polarizing beam splitter 3. The polarizing beam splitter 3 reflects s- polarized beam and passes p-polarized beam, dividing the beam that has passed the  $\lambda/2$  plate into two luminous fluxes. The p-polarized beam passing through the polarizing beam splitter 3 is reflected by a mirror 4, is reflected by a mirror 7 and by one of the reflecting planes of a roof prism 9 after the illuminating conditions are controlled by an illumination system 5, and illuminates area A on a reticle 11. On the other hand, the s-polarized beam is reflected by a mirror 8 and by the other reflecting plane of the roof prism 9 after the illuminating conditions are controlled by an illumination system 6, and illuminates area B on the reticle 11.

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